



**PATENT**

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Serial No.: 10/800,219 )  
Filed: March 12, 2004 )  
Title: Method and Apparatus for Verifying )  
the Post-Optical Proximity Corrected )  
Mask Wafer Image Sensitivity to )  
Reticle Manufacturing Errors )  
Inventors: Nadya G. Strelkova et al. )  
Art Unit: 2825 )  
Examiner: Nelson C. Lam )  
Atty. Ref: 02-2396 )

**CERTIFICATE OF MAILING**

I hereby certify that this paper is being deposited with the United States Postal Service with sufficient postage as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450 on October 2, 2006.

  
James R. Foley, Reg. No. 89,979

*Not  
Entered  
11/15/06*

**RESPONSE TO THE OFFICE ACTION MAILED JULY 31, 2006**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

Sir:

In the matter of the above-identified application and in response to the Office Action mailed July 31, 2006, kindly enter the following amendments and consider the following remarks toward reconsideration of the present application.